









## Transport along grain boundaries through alumina investigated by atom probe tomography

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Atom Probe Tomography: Zr at a grain boudary in  $Al_2O_3$ , Each dot represents one atom, Al and O atoms are not displayed



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#### **TEM of typical oxide on NiAl**





- Protective Al<sub>2</sub>O<sub>3</sub> coating on NiAl-alloy
- O (and all other elements) in α-alumina diffuse mostly via grain boundaries (GBs)
- Minor outward diffusion of metal
- Decoration of GBs will influence the diffusion and thus oxidation
- Apparently grows inwards

Material	Ni	Al	Zr	Hf	N	С	Sxx	0	В	Cr
	at.%	at.%	ррта							
Zr-doped	49.95	49.99	520	0	0	0	3	48	30	0
Hf-doped	49.83	50.07	0	480	30	36	0	43	0	100





#### **Outward diffusion: Exp. idea**

#### a) After 1<sup>st</sup> exposure







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#### **TEM of mech. pol. Hf sample**



- No Ga contamination
- GB enriched with Hf and some Ni

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#### **TEM of Zr sample**



• Zr enriched at the GB





#### How to calculate the flux

- Calculate the flux
  - Number of diffused Al-atoms  $N_{GB}^{Al}$
  - Exposure time  $\Delta t$  (10h)
  - Calculate number of atoms
    - Volume of ridge  $V^{Al} = A^{Al} L_{GB}$
    - Length of GB  $L_{GB}$  (not height!)
    - Cross section area of ridge  $A^{Al}$
    - Volume of  $Al_2O_3$  unit cell:  $V_u$ =2.54 10<sup>-22</sup> cm<sup>3</sup>
    - Number of AI atoms per unit cell: 12

$$N_{GB}^{Al} = \frac{12 V^{Al}}{V_u} \qquad J_{Al} = \frac{12 A^{Al}}{V_u}$$



 $J_{Al} = \frac{N_{GB}^{Al}}{L_{GB}\Delta t}$ 





#### Flux of Al through GBs at 1100°







## Flux of AI through GBs at 1100°



- Mech. polishing enhances ridge growth
- Zr allows higher outward flux than Hf
- Inward flux six orders of magnitude larger

Should follow Fick's 1. law (assuming  $h_{oxide}$  is constant)  $J_{GB}^{Al} = -\frac{A}{h_{oxide}}$ 





#### **APT of Hf sample**







#### **APT of Zr sample**

20 nm



- Protective Ag on top of ridge-GB
- No Ni found
- $\Gamma_{Zr}$ : 2.5 nm<sup>-2</sup>







#### **Outward flux of Ni, Hf, Zr**







## Outward flux of Ni, Hf, Cr





#### Conclusions

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- Outward Diffusion of AI along Al<sub>2</sub>O<sub>3</sub> GBs is observed by STEM Mechanical polishing introduces defects that promote diffusion
  - Hf reduces Al-outward diffusion stronger than Zr
- Zr is enriched at GBs  $\rightarrow$  Outward diffusion of Zr, Hf
- Hf is enriched at GBs
- Ni is found at the GB and at the top of the ridge in the Hf sample
  → Outward diffusion of Ni
- $J_{\rm O} \sim 10^6 \,\mathrm{nm^{-1}s^{-1}} >> J_{\rm Al} \sim 1 \,\mathrm{nm^{-1}s^{-1}} >> J_{\rm Hf,Ni,Zr} \sim 10^{-3} \,\mathrm{nm^{-1}s^{-1}}$





# Thank you for your attention

You also want APT results: knmf.kit.edu, or contact me KNMF grants APT time to suitable projects

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